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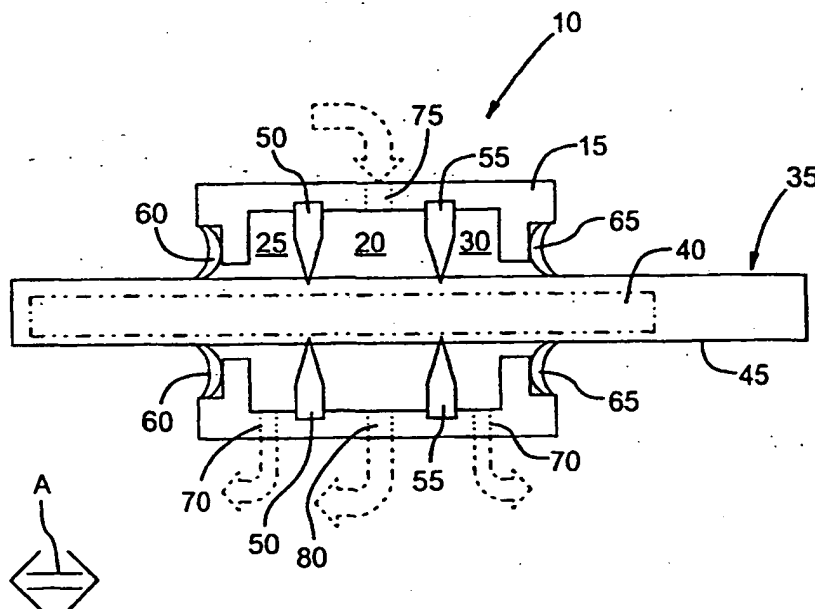
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(54) Title: FLUID TREATMENT SYSTEM AND CLEANING APPARATUS THEREFOR



(57) Abstract: A cleaning apparatus (10) for a radiation source assembly (35) in a fluid treatment system is described. The cleaning apparatus comprises cleaning chamber (20) and a second chamber (25, 30) independent of the cleaning chamber which defines a fluid (typically water) buffer layer to obviate or mitigate cleaning fluid from the cleaning chamber leaking into the fluid being treated. The fluid treatment system is particularly useful for us in clean water applications in which ultraviolet radiation is used to treat the water while having the advantages of in situ cleaning of the radiation source when it becomes fouled.